

09/701534

526 Rec'd PCT/PTO 30 NOV 2000

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

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Satoru MIYASHITA, Masahiro FURUSAWA,
Ichio YUDASAKA, Yasuo MATSUKI,
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Application No.: U.S. National Stage of
PCT/JP00/01987

Filed: November 30, 2000

Docket No.: 107291

For: METHOD FOR FORMING SILICON FILM AND INK COMPOSITION FOR INK JET

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE ABSTRACT:

Please substitute the attached Abstract for the Abstract currently in the application.

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 1, line 1, delete "DESCRIPTION"; and

line 5, change "TECHNICAL FIELD" to --BACKGROUND OF THE

INVENTION--;

between lines 5 and 6, insert --1. Field of the Invention--;

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